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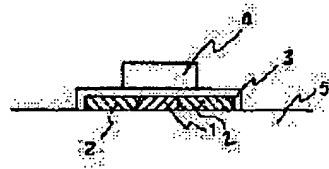
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| (21)Application number : 03-312751 | (71)Applicant : SEIKO EPSON CORP |
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(54) ACTIVE MATRIX SUBSTRATE

(57)Abstract:

PURPOSE: To reduce leakage current from a picture element additional capacity part as one of the causes of defective inhomogeneous contrast between picture element units of an active matrix liq. crystal panel.

CONSTITUTION: This active matrix substrate has a picture element electrode for driving a liq. crystal and an active switching element for driving the liq. crystal. Additional capacity is formed between a thin silicon film 2 electrically connected to the picture element electrode and an electric conductive thin film electrode 4 disposed on the film 2 with a gate SiO₂ film 3 in-between. This capacity is independent of the capacity of the liq. crystal between the picture element electrode and a counter electrode. The silicon film 1 under the electrode 4 is doped with impurity atoms.



LEGAL STATUS

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